

<p style="text-align: center;"> <b>O I P E</b>  <small>SEARCHED</small>  <b>INFORMATION DISCLOSURE</b>  <b>STATEMENT BY APPLICANT</b>          Form SB/08A  <small>(Use several sheets if necessary)</small> </p> <p style="text-align: right;">  </p>			<b>COMPLETE IF KNOWN</b>	
			Application Number	10/721,495
			Confirmation Number	
			Filing Date	November 25, 2003
			First Named Inventor	Michael Kenny
			Group Art Unit	
			Examiner Name	
1	of	1	Attorney Docket No.	54008.8100.US01 (P01-0015US2)

## **U.S. PATENT DOCUMENTS**

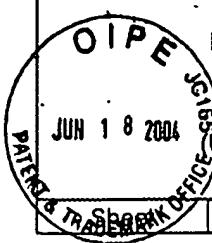
## **FOREIGN PATENT DOCUMENTS**

#### **OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume issue number(s), publisher, city and/or country where published.	T

EXAMINER 	DATE CONSIDERED 9/30/08
• EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance <u>and</u> not listed in the "List of Citations Considered" section. (See "MPEP § 609.02 regarding the use of the term 'considered'.)	

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INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT  
Form PTO-1449 (Modified)  
Use several sheets if necessary)

**COMPLETE IF KNOWN**

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1 of 4

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Examiner Initials*	Cite No.	U.S. Patent or Application		Name of Patentee or Inventor of Cited Document	Date of Publication or Filing Date of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		NUMBER	Kind Code (if known)			
JWS	DO	6,551,409		DeGendt	04/22/03	
JWS	DP	2002/0011257		DeGendt	01/31/02	

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JWS	DQ	Alder, M., et al., "The Kinetics and Mechanism of Hydroxide Ion Catalyzed Ozone Decomposition in Aqueous Solution." <i>J. Am. Chem. Soc.</i> , 72:1884-1886 (1950).	
	DR	Amick, J.A., "Cleanliness and the Cleaning of Silicon Wafers." <i>Solid State Technology</i> , pp. 47-52 (Nov. 1976).	
	DS	Anantharaman, et al., "ORGANICS: Detection and Characterization of Organics in Semiconductor DI Water Processes." <i>Ultrapure Water</i> , pp. 30-36 (Apr. 1994).	
	DT	Baumgärtner, H., et al., "Ozone Cleaning of the Si-SiO <sub>2</sub> System." <i>Appl. Phys. A</i> , 43:223-226 (1987).	
	DU	Bedge, S., et al., "Kinetics of UV/O <sub>2</sub> Cleaning and Surface Passivation: Experiments and Modeling." <i>Mat. Res. Soc. Symp. Proc.</i> , 259:207-212 (1992).	
	DV	Bolon, D.A., et al., "Ultraviolet Depolymerization of Photoresist Polymers," <i>Polymer Engineering and Science</i> , 12(2):108-111 (March 1972)	
JWS	DW	Christenson, K., et al., "Deionized Water Helps Remove Wafer Stripping 'Resist'-ance." <a href="http://www.precisioncleaningweb.com--Precision Cleaning Web-Archives">www.precisioncleaningweb.com--Precision Cleaning Web-Archives</a> , pp. 10-20 (Apr. 1998).	

EXAMINER	DATE CONSIDERED
<i>JWS</i>	4/30/04

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MWS	DX	Egitto, F.D., et al., "Removal of Poly (Dimethylsiloxane) Contamination From Silicon Surfaces With UV/Ozone Treatment." <i>Mat. Res. Soc. Symp. Proc.</i> , 385:245-250 (1995).			
	DY	Gabriel, C., et al., "Reduced Device Damage Using An Ozone Based Photoresist Removal Process." <i>SPIE Advances in Resist Technology and Processing VI</i> , 1086:598-604 (1989).			
	DZ	Ganesan, G., et al., "Characterizing Organic Contamination in IC Package Assembly." <i>The Int'l. Soc. for Hybrid Microelectronics</i> , 17(2), Second Quarter, 152-160 (1994).			
	EA	Golland, D.E., et al., "The Clean Module: Advanced Technology for Processing Silicon Wafers." <i>Semiconductor Int'l.</i> , pp. 154-157 (Sep. 1987).			
	EB	Goulding, M.R., "The selective epitaxial growth of silicon," <i>Materials Science and Engineering</i> , Vol. B17, pp. 47-67 (1993).			
	EC	Heyns, M.M., et al., "New Wet Cleaning Strategies for Obtaining Highly Reliable Thin Oxides." <i>MRP Symposium Proceedings on Materials Research Society</i> , Spring Meeting, San Francisco, CA, Apr. 12-13, p. 35 (1993).			
	ED	Huynh, C., et al., "Plasma versus ozone photoresist ashing: Temperature effects on process-induced mobile ion contamination." <i>J. Vac. Sci. Technol.</i> , B9(2):353-356 (Mar./Apr. 1991).			
	EE	Isagawa, T., et al., "Ultra Clean Surface Preparation Using Ozonized Ultrapure Water." <i>Extended Abstracts of the 1992 Int'l. Conf. on Solid State Devices and Materials</i> , pp. 193-195 (1992).			
	EF	Kasi, S., et al., "Surface Hydrocarbon Removal from Si by UV/Ozone." <i>ECS Extended Abstracts</i> , No. 458, pp. 691-692 (1990).			
	EG	Kasi, S., et al., "Vapor phase hydrocarbon removal for Si processing." <i>Appl. Phys. Lett.</i> , 57(20):2095-2097 (Nov. 1990).			
MWS	EH	Kern, W., "The Evolution of Silicon Wafer Cleaning Technology." <i>J. Electrochem. Soc.</i> , 137(6):1887-1892 (Jun. 1990).			

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	4/30/06
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[54008.8100.US01/LA041610.019]	

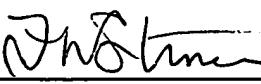
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				Filing Date	November 25, 2003
				First Named Inventor	Michael KENNY
				Group Art Unit	
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<i>JWS</i>	EI	Krusell, W.C., et al., "Cleaning Technologies for High Volume Production of Silicon Wafers." <i>ECS Proc. of the First Int'l. Symposium on Cleaning Technology in Semiconductor Device Mfg.</i> , pp. 23-32 (Oct. 1989).			
	EJ	Krusell, W.C., et al., "The Characterization of Silicon Substrate Cleaning Treatments by use of SIMS and MOS Electrical Testing." <i>ECS Extended Abstracts</i> , No. 229, p. 331-332 (1986).			
	EK	Nelson, S., "Ozonated water for photoresist removal." <i>Solid State Technology</i> , p. 107-112 (Jul. 1999).			
	EL	Ohmi, T., et al., "Native Oxide Growth and Organic Impurity Removal on Si Surface with Ozone-Injected Ultrapure Water." <i>J. Electrochem. Soc.</i> , 140(3):804-810 (Mar. 1993).			
	EM	Sehested, K., et al., "Decomposition of Ozone in Aqueous Acetic Acid Solutions (pH 0-4)." <i>J. Phys. Chem.</i> , pp. 1005-1009 (1992).			
	EN	Shimada, H., et al., "Residual-Surfactant-Free Photoresist Development Process." <i>J. Electrochem. Soc.</i> , 139(6):1721-1730 (Jun. 1992).			
	EO	Suemitsu, M., et al., "Low Temperature Silicon Surface Cleaning by HF Etching/Ultraviolet Ozone Cleaning (HF/UVOC) Method (I)-Optimization of the HF Treatment." <i>Japanese Journal of Applied Physics</i> , 28(12):2421-2424 (Dec. 1989).			
	EP	Tabe, M., "UV ozone cleaning of silicon substrates in silicon molecular beam epitaxy." <i>Appl. Phys. Lett.</i> , 45(10):1073-1075 (Nov. 1984).			
	EQ	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>ECS Extended Abstracts</i> , Phoenix, AZ, Abstract No. 506, pp. 753 (Oct. 13-17, 1991).			
	ER	Tong, J., et al., "Aqueous Ozone Cleaning of Silicon Wafers." <i>Proc. of 2.sup.nd Int'l. Symposium on Cleaning Tech. In Semiconductor Device Mfg.</i> , pp. 18-25 (Oct. 1992).			
	ES	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Elec. Tech. and Devices Lab.</i> , pp. 1-26.			
<i>JWS</i>	ET	Vig, J., "UV/Ozone Cleaning of Surfaces: A Review." <i>Surface Contamination: Genesis, Detection, and Control</i> , pp. 235-253 (1979).			

EXAMINER	DATE CONSIDERED
<i>JWS</i>	7/31/06
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				First Named Inventor	Michael KENNY
				Group Art Unit	
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JNS	EU	Vig, J., et al., "UV/Ozone Cleaning of Surfaces." <i>IEEE Transactions on Parts, Hybrids, and Packaging</i> , Vol. PHP-12(4):365-370 (Dec. 1976).			T
	EV	Vig, J., "UV/Ozone Cleaning of Surfaces." <i>U.S. Army Electronics Technology and Devices Laboratory</i> , ERADCOM, Ft. Monmouth, NJ, 07703-5302, pp. 1027-1034 (Sep./Oct. 1984).			
	EW	Zafonte, L., et al., "UV/Ozone Cleaning For Organics Removal on Silicon Wafers." <i>SPIE Optical Microlithography III: Technology for the Next Decade</i> , 470:164-175 (1984).			
	EX	Zazzera, L.A., et al., "XPS and SIMS Study of Anhydrous HF and UV/Ozone-Modified Silicon (100) Surfaces." <i>J. Electrochem. Soc.</i> , 136(2):484-491 (Feb. 1989).			
	EY	"Ozone Concentration Measurement in a Process Gas." <i>Proposed IOA Pan American Group Guideline</i> , pp. 1-21 (Dec. 1993).			
JNS	EZ	"Ozone for Semiconductor Applications." <i>Sorbios</i> , pp. 1-6 (Oct. 1991).			

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[54008.8100.US01/LA041610.019]

<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> Form SB/08A (Use several sheets if necessary)				<b>COMPLETE IF KNOWN</b>	
				Application Number	10/721,485
				Confirmation Number	6048
				Filing Date	November 25, 2003
				First Named Inventor	Michael Kenny
				Group Art Unit	1746
				Examiner Name	Frankie L. Stinson
				Attorney Docket No.	54008.8100.US01 (P05-0015US2)
Sheet	1	of	4		



<b>U.S. PATENT DOCUMENTS</b>					
Examiner Initials*	Cite No.	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Inventor of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (if known)			
JWS	FB	4,064,885	12-1977	Dussault et al.	
	FC	4,633,804	01-1987	Arii	
	FD	4,695,327	09-1987	Grebinski	
	FE	4,778,532	10-1988	McConnell et al.	
	FF	4,899,767	02-1990	McConnell et al.	
	FG	5,039,349	08-1991	Schoeppel	
	FH	5,147,499	09-1992	Szwejkowski et al.	
	FI	5,423,944	03-1994	Wong	
	FJ	5,518,542	05-1996	Matsukawa et al.	
	FK	5,868,866	02-1999	Maekawa et al.	
	FL	5,911,836	06-1999	Hada et al.	
	FM	5,922,624	07-1999	Verhaverbeke et al.	
	FN	5,927,306	Jul-99	Izumi et al.	
	FO	5,975,098	11-1999	Yohitani et al.	
	FP	5,990,060	11-1999	Ohmi et al.	
	FQ	6,003,527	12-1999	Netsu et al.	
	FR	6,085,764	07-2000	Kobayashi	
	FS	6,199,567	03-2001	Kanno et al.	
	FT	6,202,658	03-2001	Fishkin et al.	
	FU	6,235,112	05-2001	Satoh	
	FV	6,240,933	06-2001	Bergman	
	FW	6,295,999	10-2001	Bran	
	FX	6,325,081	12-2001	Miki et al.	
	FY	6,406,551	06-2002	Nelson et al.	
	FZ	6,423,146	07-2002	Fukazawa	
JWS	GA	6,431,184	08-2002	Taniyama	

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				Filing Date	November 25, 2003
				First Named Inventor	Michael Kenny
				Group Art Unit	1746
				Examiner Name	Frankie L. Stinson
Sheet	2	of	4	Attorney Docket No.	S4008.8100.US01 (P05-0015US2)

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JWS	GB	6,455,717	09-2002	Vaartstra	
	GC	6,497,768	12-2002	Bergman	
	GD	6,543,080	04-2003	Tomita et al.	
	GE	6,582,525	06-2003	Bergman	
	GF	6,626,189 B2	11-25-2002 F	Kashkoush et al.	
	GG	6,743,301	12-22-2000 F	Matsuno et al.	
	GH	6,817,370	11-2004	Bergman et al.	
	GI	6,843,857	01-2005	Bergman	
	GJ	6,869,487	03-2005	Bergman	
	GK	2002/0066464 A1	06-2002	Bergman	
JWS	GL	2004/0154641 A1	08-12-2004	Montierth	

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		Country Code	Number-Kind Code (if known)				
JWS	GM	DE	19801360 A1	7/22/1999	SEZ Semiconductor-Equipment Zubehor		
	GN	EP	0 587 889	03-23-1994	Ohmi, Tadahiro		
	GO	EP	0 890 658	01-1999			
	GP	GB	2 287 827	09-27-1995	NEC Corporation		
	GQ	JP	01-189921	07-31-1989	Mitsubishi Electric Corp.		
	GR	JP	04-079221	03-12-1992	Seiko Epson Corp.		
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	GV	JP	08-288271	11-1996			
	GW	JP	08-064566	03-08-1996	Ryoden Semiconductor		
	GX	JP	09-139345	05-1997			
	GY	JP	10-144640	05-1998			
	GZ	JP	11-054427	02-1999			
	HA	JP	59-068930	04-1984			
	HB	JP	61-004232	01-10-1986	NEC Corp.		
	HC	JP	2000-138188	05-2000			
AJNS	HD	WO	WO01/07177 A1	02-01-2001	Semitool, Inc.		

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(JWS)	HE	Bergman, E. et al., "HF-Ozone Cleaning Chemistry," Solid State Technology 46(7):115-124(2001)	

*JWStinson 4/26/06*